

SUMEC
苏美达能源

SUMEC Energy Holdings Co., Ltd.

 国机集团
SINOMACH | **SUMEC**

NANJING . CHINA 2017.03

SUMEC
苏美达能源

Research and development of advanced photovoltaic technologies at Phono Solar: Black silicon, MWT and SHJ

PART 1
About us

PART 2
R&D Progress

PART 3
PV Plant case

PART 1. About us

- SINOMACH
- SUMEC Group & SUMEC Energy Holdings Co., Ltd.
- SINOMACH New Energy Research Institute

About SINOMACH



- Established **in January 1997**
- **A class** state-owned enterprise
- Fortune Global **500** enterprises
- **180+** overseas branches
- **35.1 billion** USD business revenue
- **Over 120,000+** employees

Core business



R&D and
Manufacture



Project
Contracting



Trade and
Services



Financing &
Investment

About SUMEC

SUMEC

- Established **in 1978**
- A **key member** of SINOMACH
- **Central government-owned** enterprises in Jiangsu province
- **5.7 billion** USD business revenue
- **10,000+** employees

Core business



**Trade &
service**



**R&D &
Engineering**



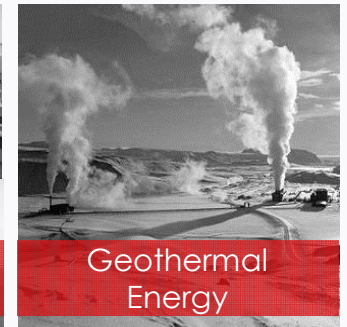
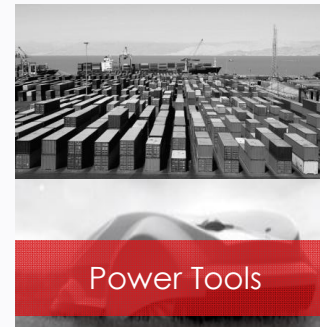
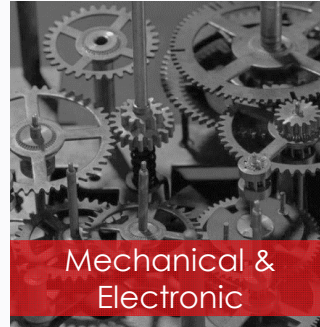
**Investment
& development**

About SUMEC



Globalized Industry Platform

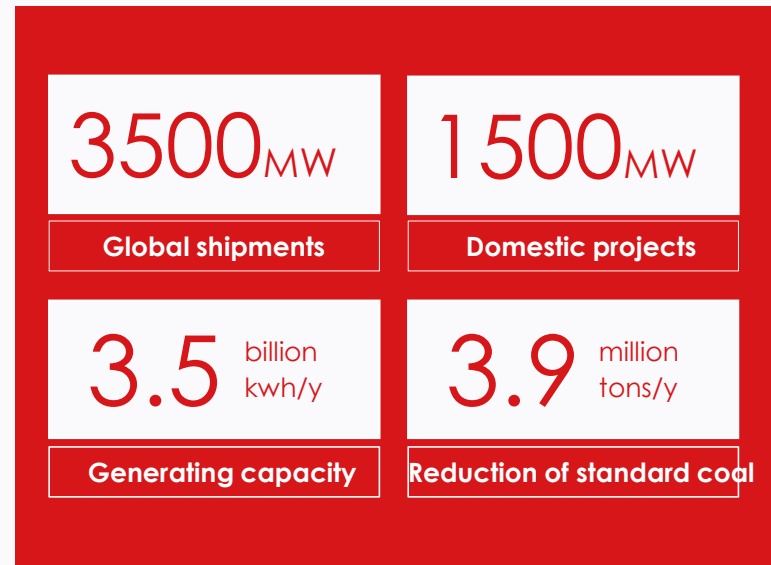
About SUMEC



About SUMEC Energy

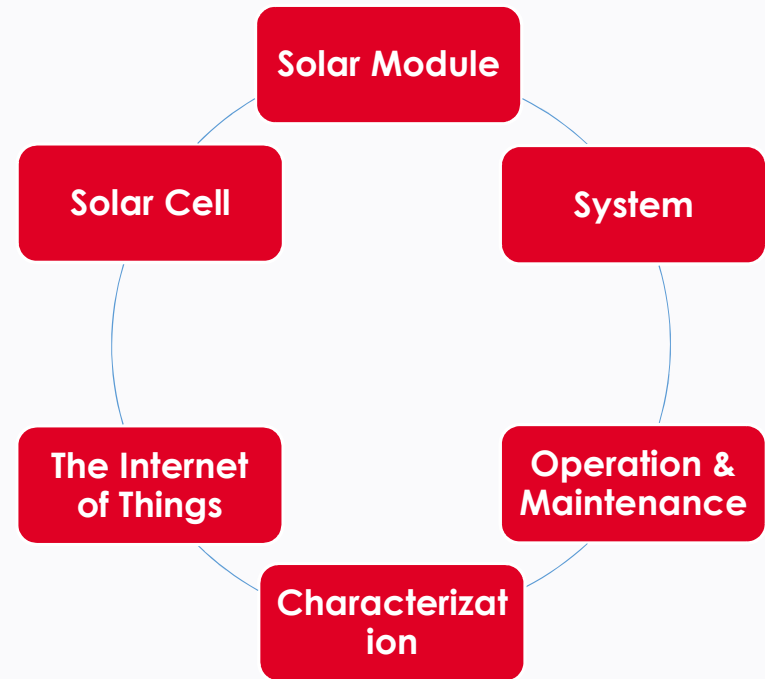
SUMEC Energy, a leading global provider of clean energy solutions, committed to customer centered solutions for Energy Supply, Energy Management, Energy Saving and Energy Storage

SUMEC Energy in order to provide efficient and economically sustainable solutions, uses extensive and innovated supply chain strategies, principles and techniques

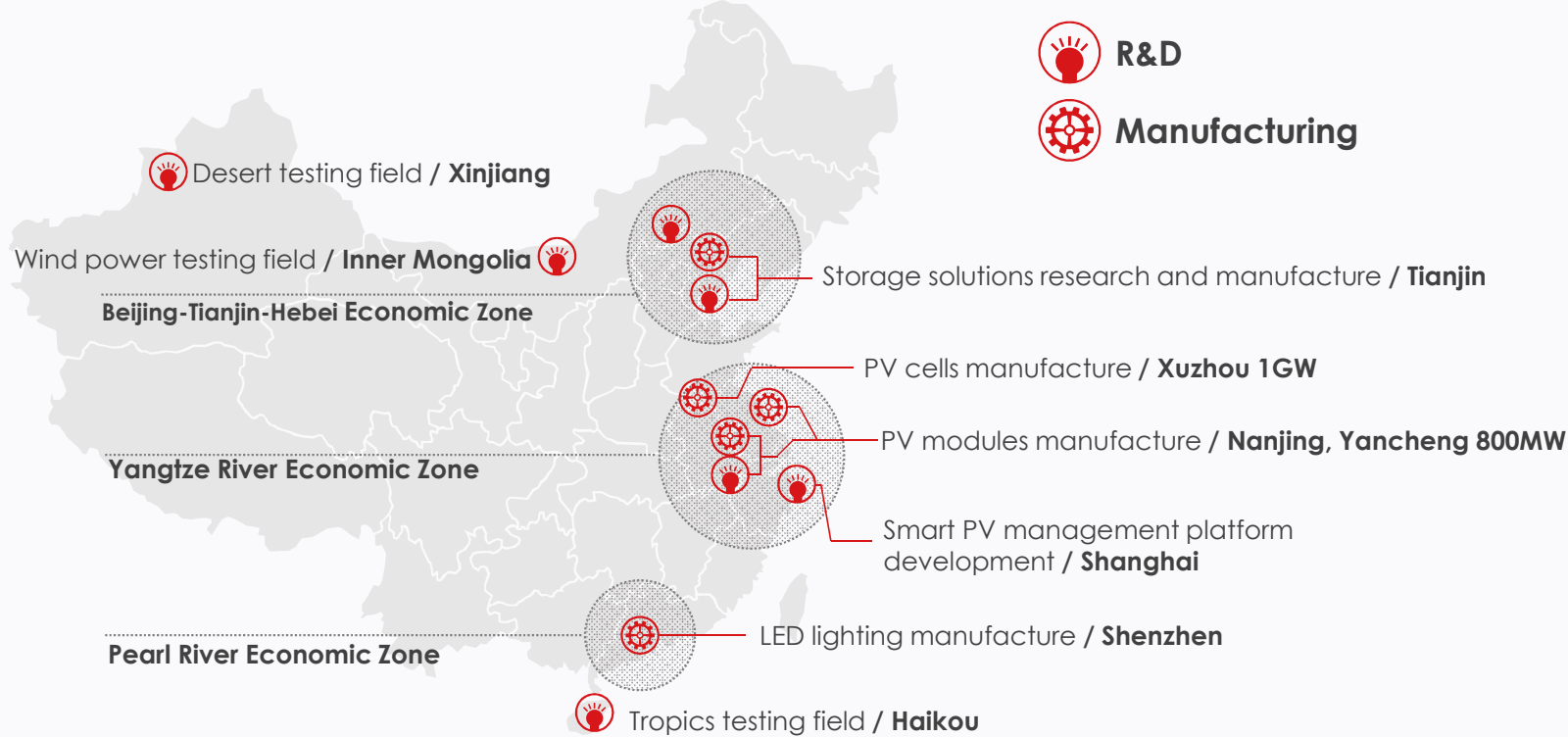


About SINOMACH New Energy Research Institute

A **close loop capability system** for **reducing the cost per kilowatt hour** of PV generated power



R&D and Manufacturing Base



Manufacturing

Tier 1
Bloomberg
NEW ENERGY FINANCE

PV Module Maker Tiering System

Phono[®] Solar

1000_{MW}
Production capacity



3500_{MW}
Global shipments



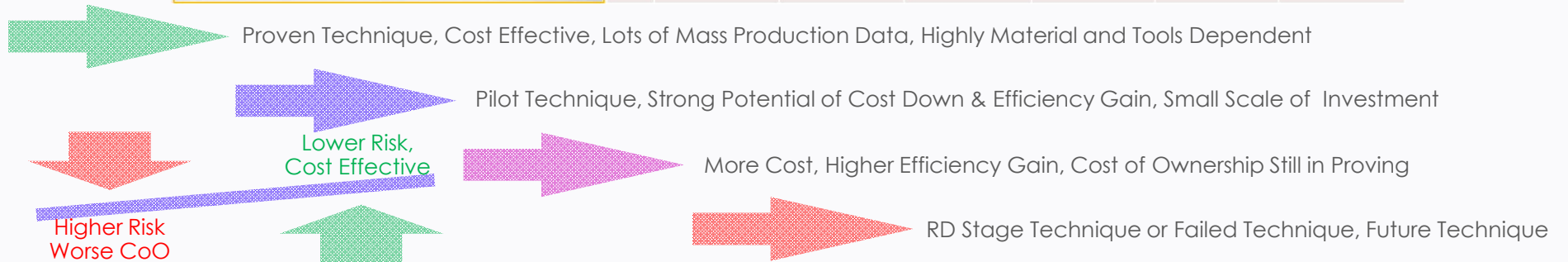
Phono Solar Technology Co., Ltd., was founded by SUMEC Group Corporation. Phono Solar is leading brand in the clean energy industry, providing high efficiency PV modules since 2004.

PART 2. R&D Progress

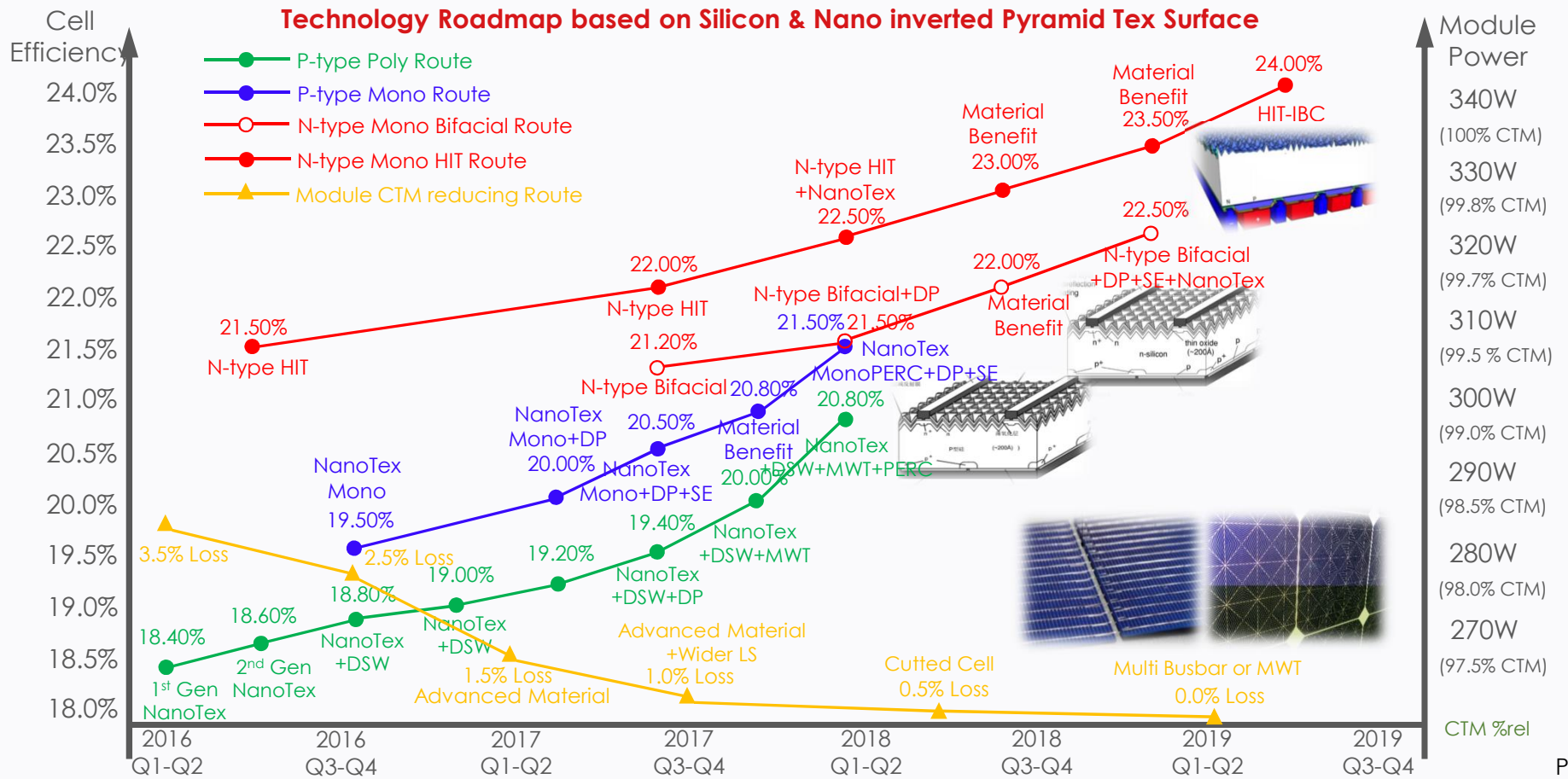
- Strategy & Technology Roadmap
- Nano-Texturing
- Metal Wrap Through Technology
- HJT Technique & Performance
- PERC+ Research
- PV System Forecasting

Strategy & Technology Roadmap

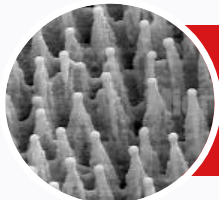
Classical Silicon based Solar Cell					Wafer	Texturing	Diffusion	PSG/ISO	Passivation	Printing /Firing
					Step 1	Step 2	Step 3	Step 4	Step 5	Step 6
					DSW	Nano Texturing	Selective Emitter			Double Print/Multi Busbar
Front										
Emitter	Pure Material/N type wafer		Ion Implantation							
Rear			Bifacial Diffusion	Rear Side Polishing	Rear Side Passivation					MWT



Strategy & Technology Roadmap

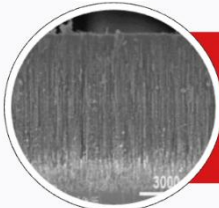


Nano-Texturing



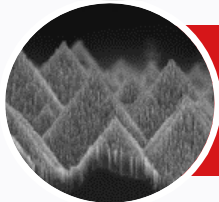
Femtosecond Laser Etching

Nano spike structure , high cost , surface damage



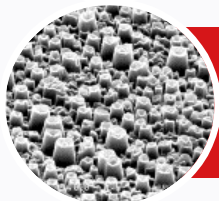
Electrochemical Etching

Porous structure , complex process



Metal Assisted Chemical Etching (MACE)

Nanowires or nanopores , anisotropic etching , low cost

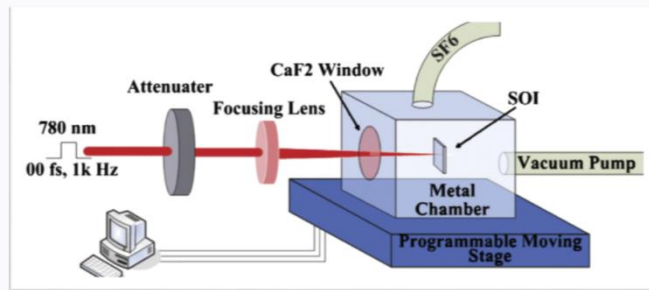


Reactive Ion Etching (RIE)

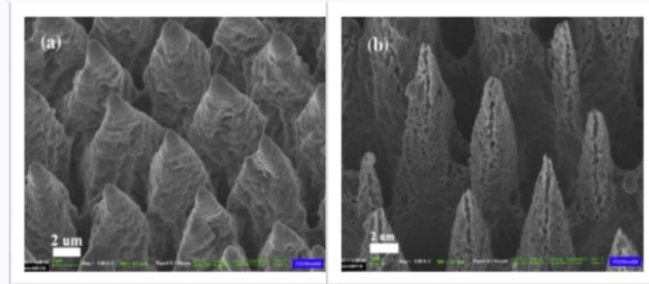
Nanocones or nanopillars , plasma etching , high equipment cost

Nano-Texturing

Femtosecond Laser Etching

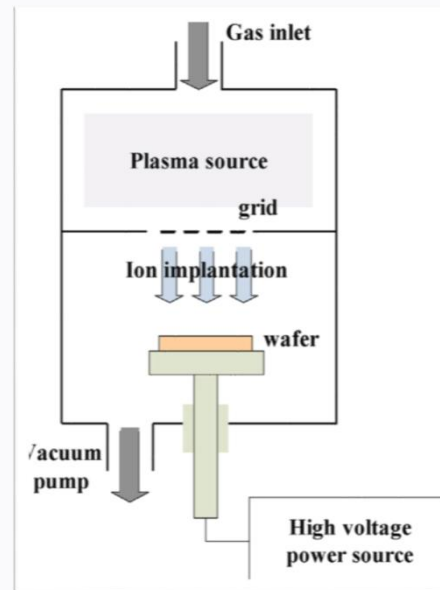


Schematic diagram of the experimental setup for the flexible black silicon fabrication

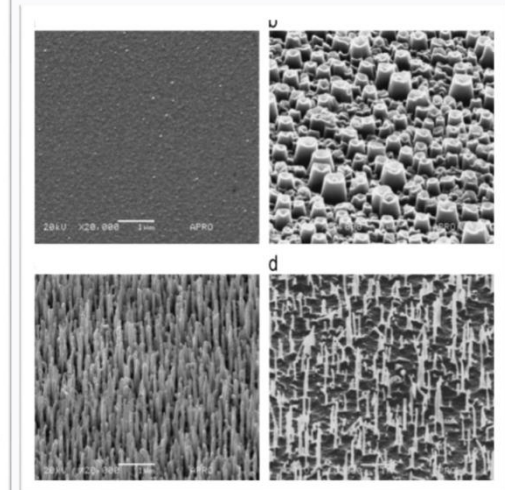


Scanning electron microscope (SEM) image of the micro spike structure of the fabricated flexible black silicon

Reactive Ion Etching (RIE)



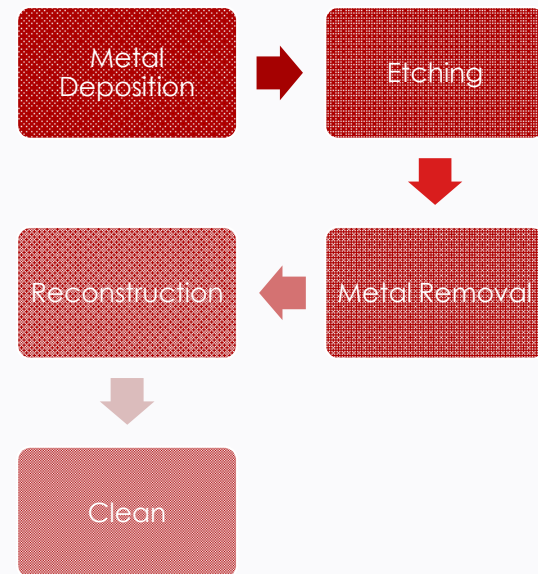
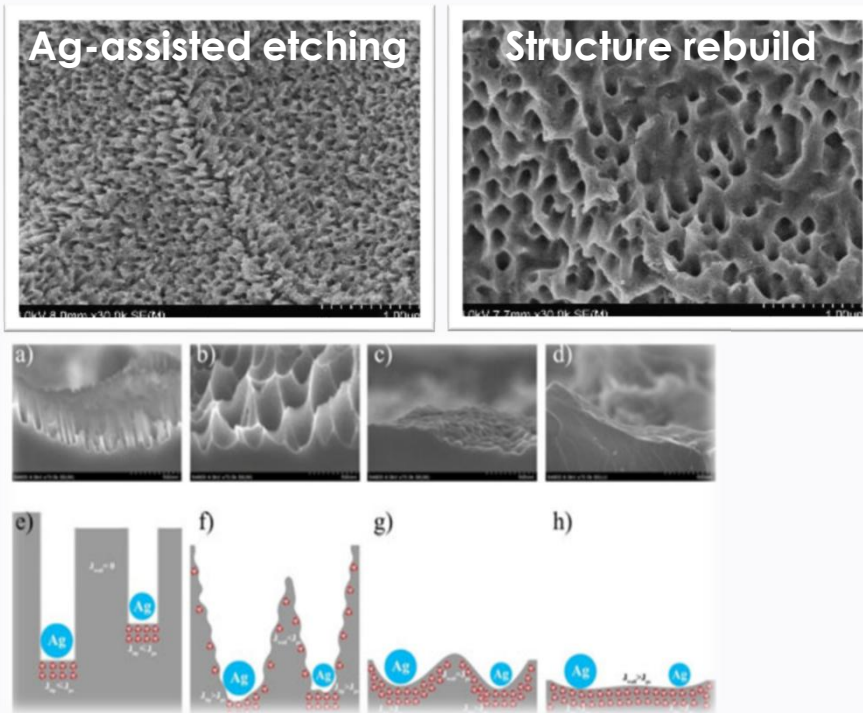
Schematic illustration of a DC-plasma immersion ion implantation apparatus



SEM images of silicon surface structures formed by RIE processing with different SF₆/O₂ gas flow ratios

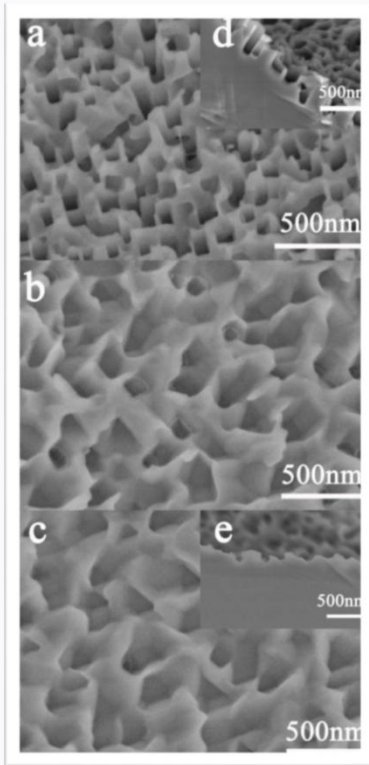
Nano-Texturing

Metal Assisted Chemical Etching (MACE)

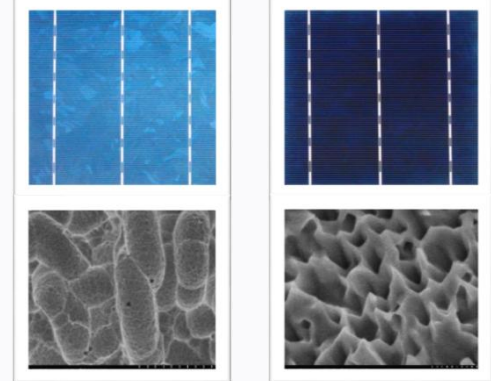
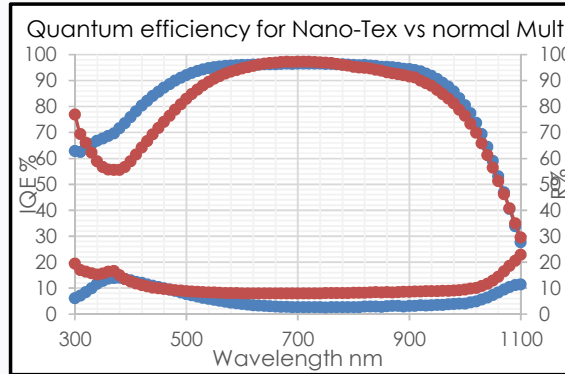


Schematic of Nano-textured silicon processing steps.

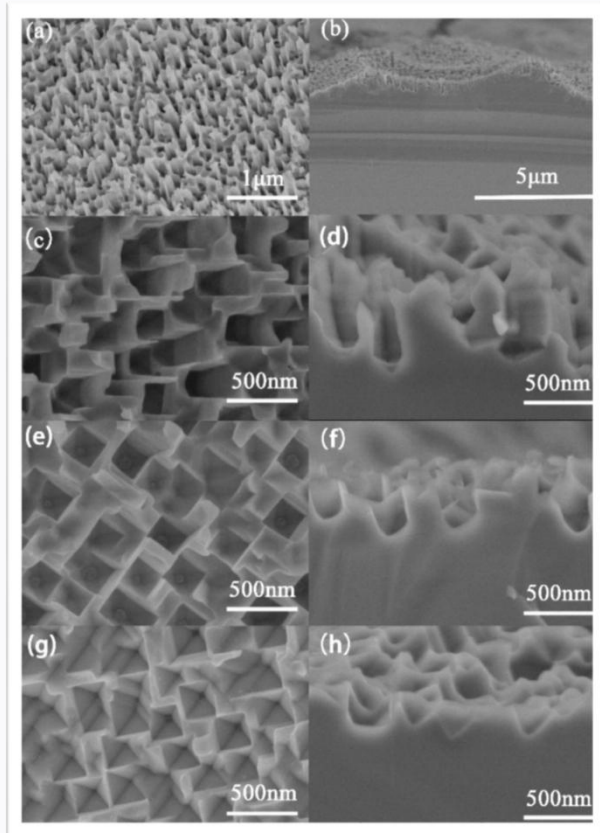
Nano-Texturing



	Voc (V)	Isc (A)	Rs (mΩ)	FF (%)	Eff (%)
Acid textured (avg.)	0.630	8.647	0.0029	78.61	17.59%
Alkaline treatment Nano-mc-Si (avg.)	0.629	8.738	0.0024	79.19	17.89%
Round treatment Nano-mc-Si (avg.)	0.630	8.764	0.0029	79.02	17.94%
Best Nano-mc-Si	0.634	8.882	0.0023	79.78	18.47%



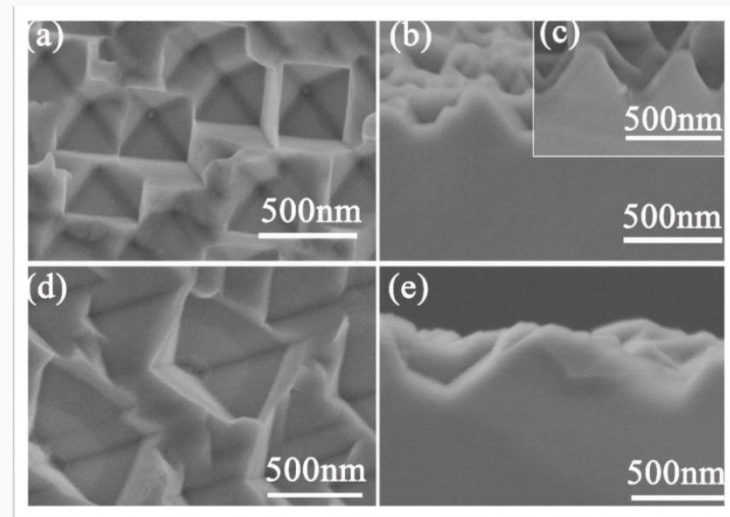
Nano-Texturing



SEM images of the nanostructure after NSR treatment under different time

Inverted pyramid structure by NSR

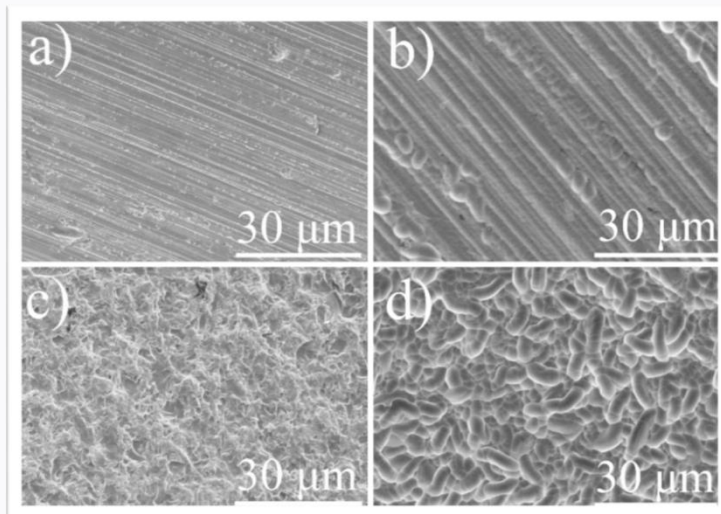
Nano Structure Rebuilding (NSR) solution
 Based on acid system
 H_2O_2 and additive



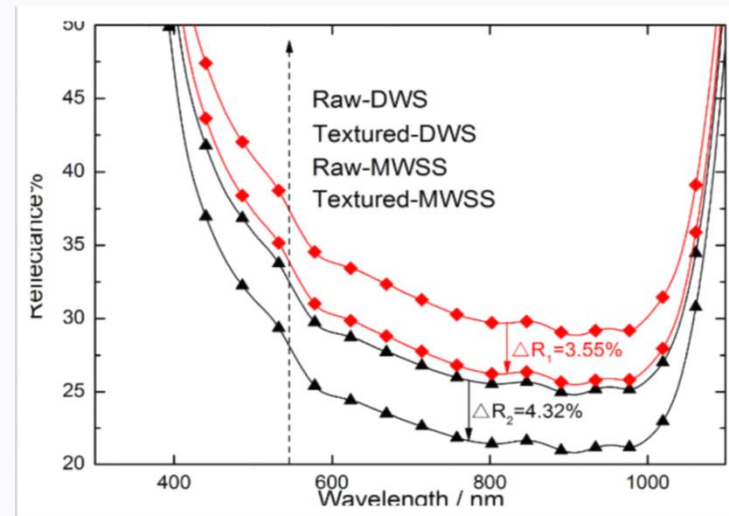
SEM images of the inverted pyramids with further NSR treatment

Nano-Texturing

Diamond Wire Sawed Wafer

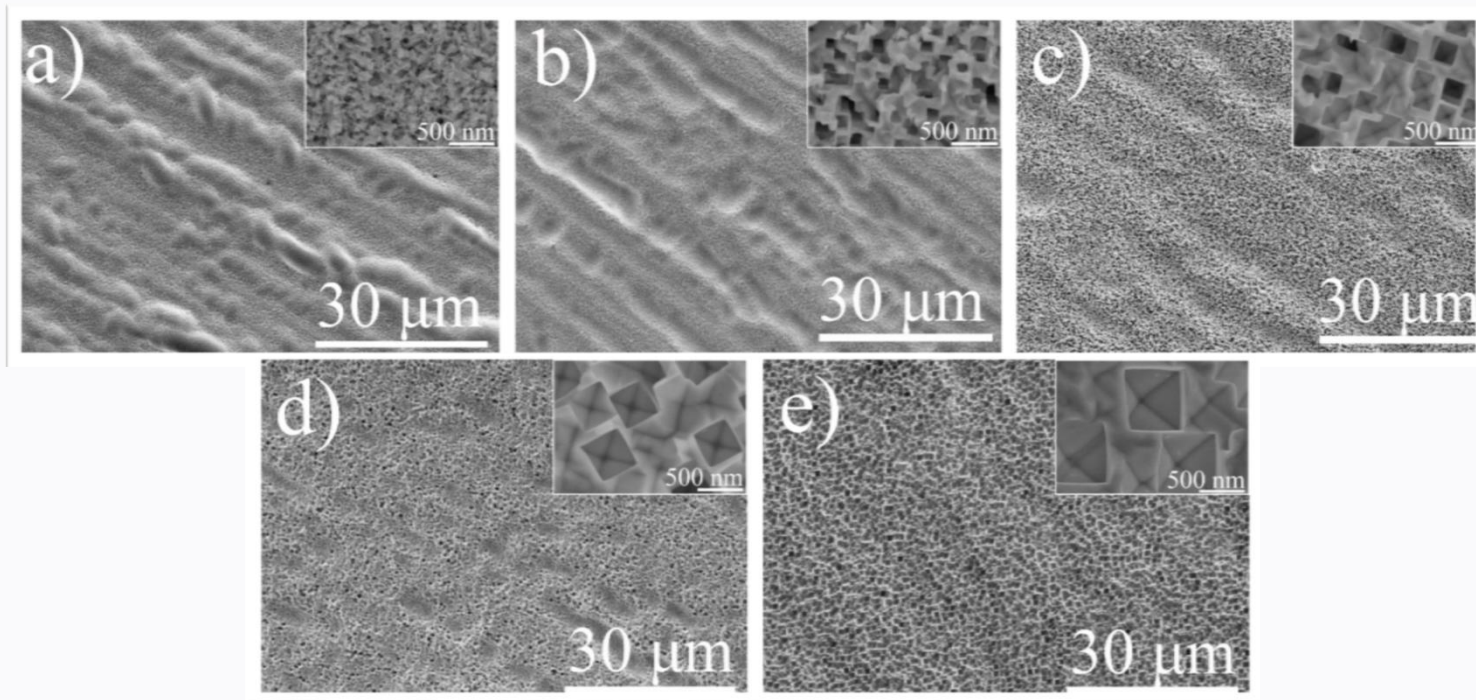


Surface SEM figures of acid texture on DWS and MWSS wafers



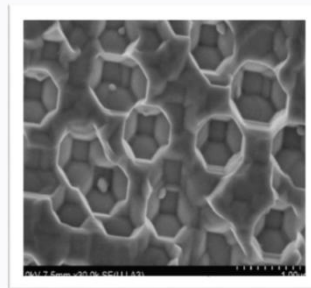
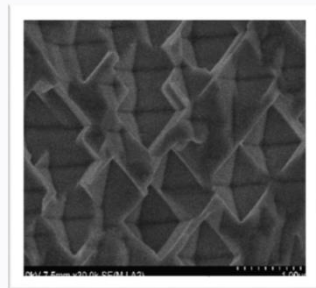
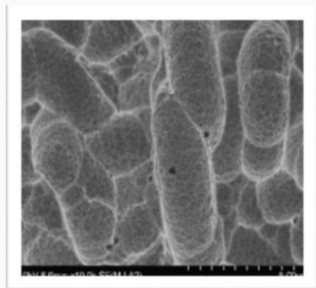
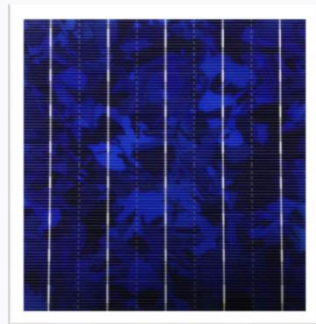
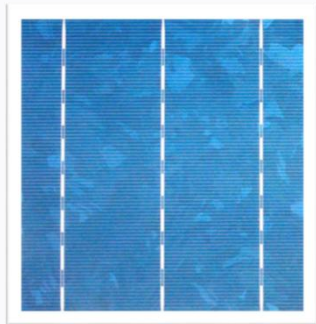
Reflectance of DWS and MWSS wafers before and after acid texture

Nano-Texturing



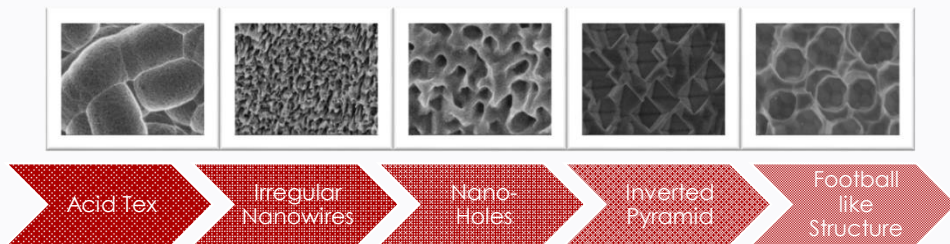
Surface SEM figures of DWS wafers with different NSR treatment time

Nano-Texturing

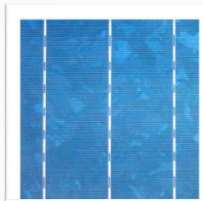


Mass Production Nano-Texturing Multi Solar cell & Module based on Dimond Saw Wafer

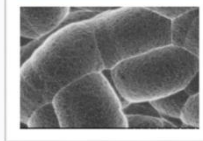
Nano-Texturing



Index for SUMEC's Nano-Tex Solar Cell

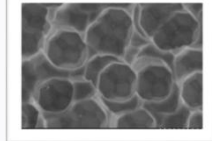
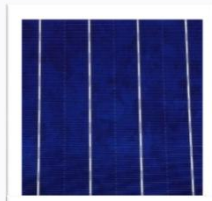


- ◆ Cell
 - 1) Cell Cost Down 5%
 - 2) Compatible with DWS wafer
 - 3) Compatible with other High Efficiency Technologies
 - 4) Efficiency Gain 0.4%



- ◆ Module
 - 1) Module Cost Down 4%

- ◆ System
 - 1) Power Output Gain (kwh/kw) is over 3%
 - 2) System Cost Down 3%



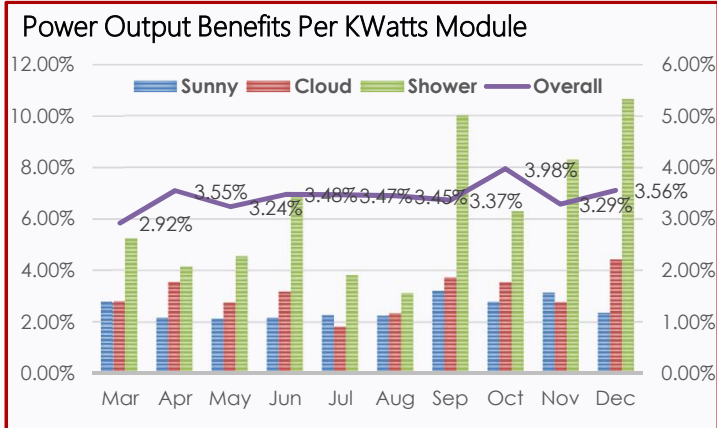
	Acid Tex	Nano-Tex
Chemical (\$/W)	0.002	0.006
Tool, Consumption, Labour Cost (\$/W)	0.0007	0.002
Total Cost (\$/W)	0.0027	0.008
Cost Saving from Wafer (\$/W)	0 (Slurry)	0.013 (Diamond)
The Real Cost Down or Increase (\$/W)	0.0027 (Increase)	0.005 (Down)
Efficiency Gain	0%	+0.4%
Income (\$/W)	—	0.023
Total Income (\$/W)	—	0.028
Module Cost	—	3.5% (Down)
System Cost	—	2.4% (Down)
Power Cost per Kwh	—	5% (Down)

Nano-Texturing

Power Plant: SUMEC HQ; Location: Nanjing
 Type: distributed system; Capacity: 1.1MW



Power Plant: SUMEC Bao Fengda YangZhou; Location: (33.37786N,119.52888E)
 Type: Ground-based solar system; Capacity: 9MW



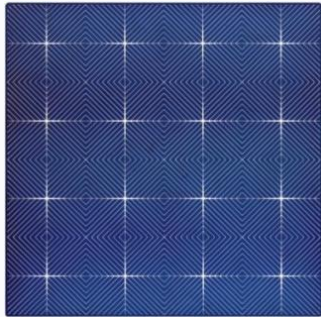
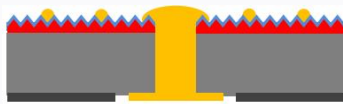
Time/ Capacity	Normal Multi 260P					Nano-Tex 260P	Nano-Tex/ Normal
	Array #1 (1510KW)	Array #2 (1510KW)	Array #3 (1510KW)	Array #4 (1510KW)	Avg (1510KW)	Array #5 (1478KW)	
Jul	110.577	110.065	110.094	108.673	109.852	112.735	2.62%
Aug	114.499	113.878	113.808	111.573	113.440	116.709	2.88%
Sep	128.228	127.055	127.057	122.925	126.316	132.354	4.78%
Oct	103.370	102.733	102.809	100.124	102.259	106.659	4.30%
Nov	43.769	43.510	43.554	42.891	43.431	44.704	2.93%
Dec	73.595	72.822	73.136	71.169	72.680	75.053	3.26%
Sum	647.631	642.884	643.594	628.524	640.658	663.267	3.53%

Nano-Texturing

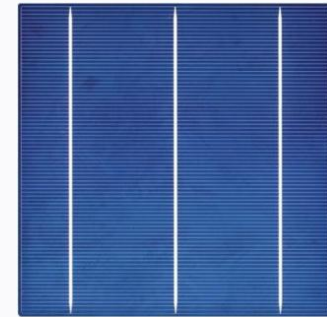
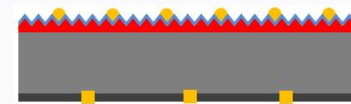


Technical Indicator		Mass Production	2nd Generation
Tools	Through put(pc/H)	3400	5000+
	Uptime	88%	92%
	Investment (\$)	430,000	580,000
	Automation	fully	fully
Process	Wafer Cutting	Slurry & diamond	Slurry & diamond
	Wafer	multi & mono	multi & mono
	Efficiency Gain(multi)	0.4%(19.00%)	0.4%(19.00%)
Module	CTM	~1.5% , +5 ~ +10W	~1% , +10W
	Reliability & Stability	good	good
	Power Output per KW Gain	+3%	+3%

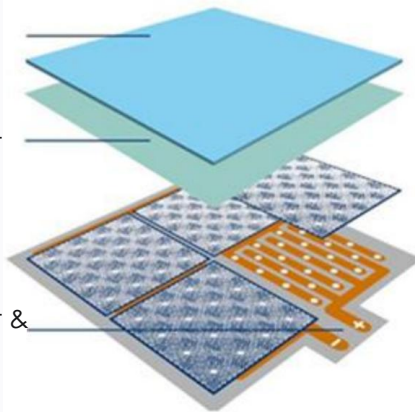
Metal Wrap Through Technology



MWT	Contrast items	Normal
Wrapped-through	Cell Structure	Front electrode
No busbar	Front Grid	Busbar
Better appearance		monotonous appearance
Less	Grid Shading	More
+0.3%	Efficiency Gain	0%
Patterned conductive foil integrated backsheet	Module assembling	normal backsheet
Electrical conductive adhesive(Less CTM)		Welding strip(Higher Rs Loss)
Compatible with IBC & thin wafer		None Compatible with IBC & thin wafer



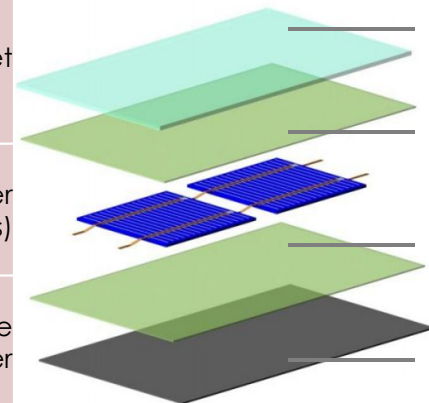
Front Sheet



Encapsulant

Encapsulant & BackSheet

Front Sheet

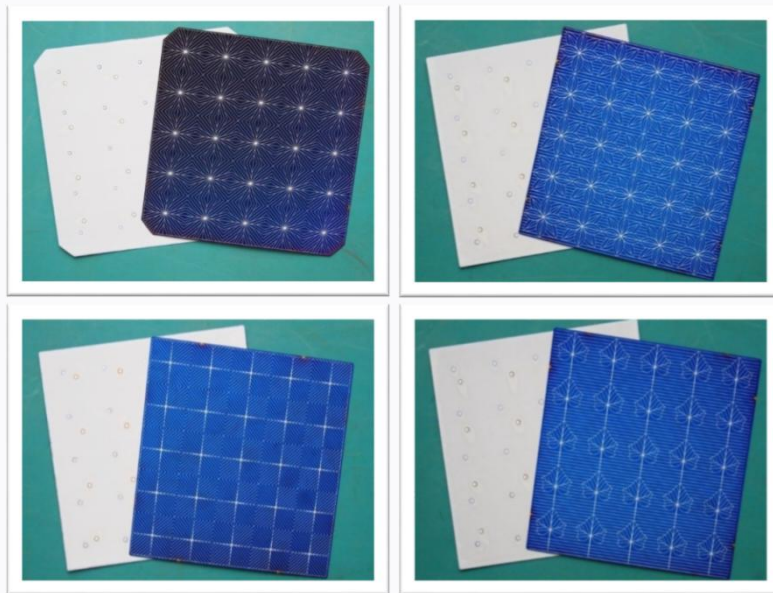


Encapsulant

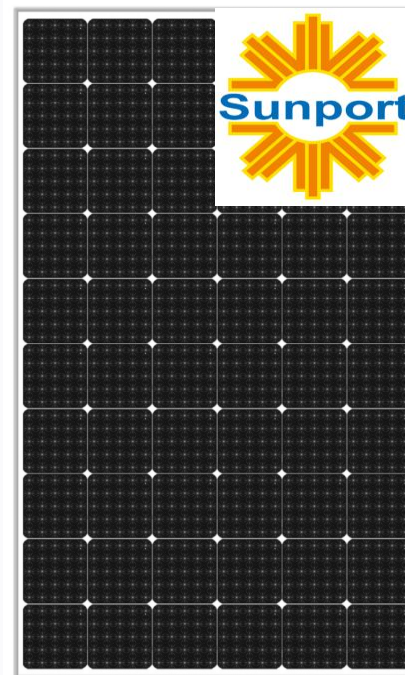
Encapsulant

Back Sheet

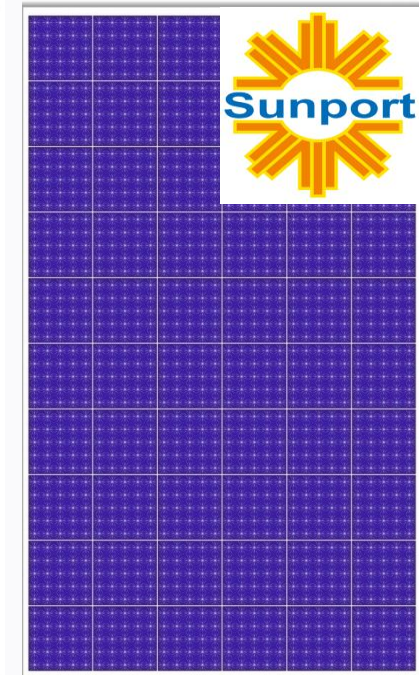
Metal Wrap Through Technology



- ❑ Front side 25 holes by laser drilled → Future 36 holes
- ❑ Average efficiency for normal multi wafer & process → 19.0%
- ❑ We are doing process integration with Nano-Tex multi cells, the average cell efficiency might achieve over 19.5%
- ❑ Our power output target for the 60p@module is 300Wp



Mono 60pcs MWT module
(Normal Mono ~ 280Wp, MWT Mono ~ 295Wp)



Multi 60pcs MWT module
(Normal Multi ~ 270Wp, MWT Multi ~ 285Wp)

Metal Wrap Through Technology

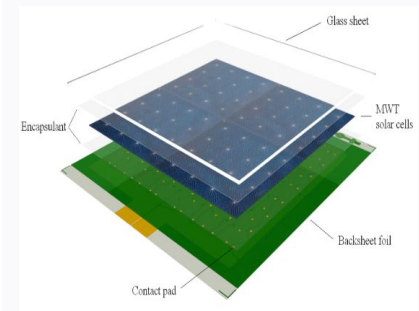
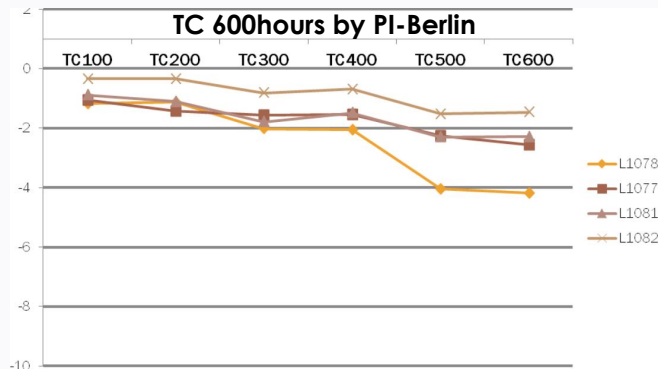
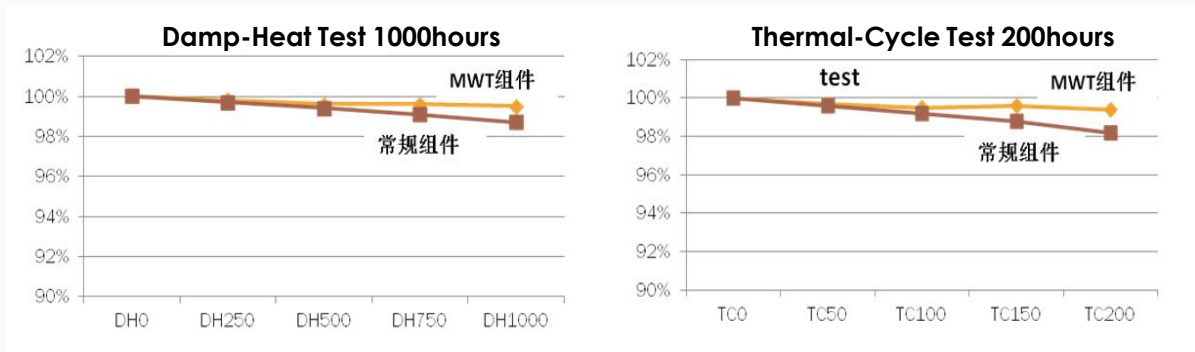
MWT reliability & stability test

DH Condition:

1000hours@85°C & 85%RH

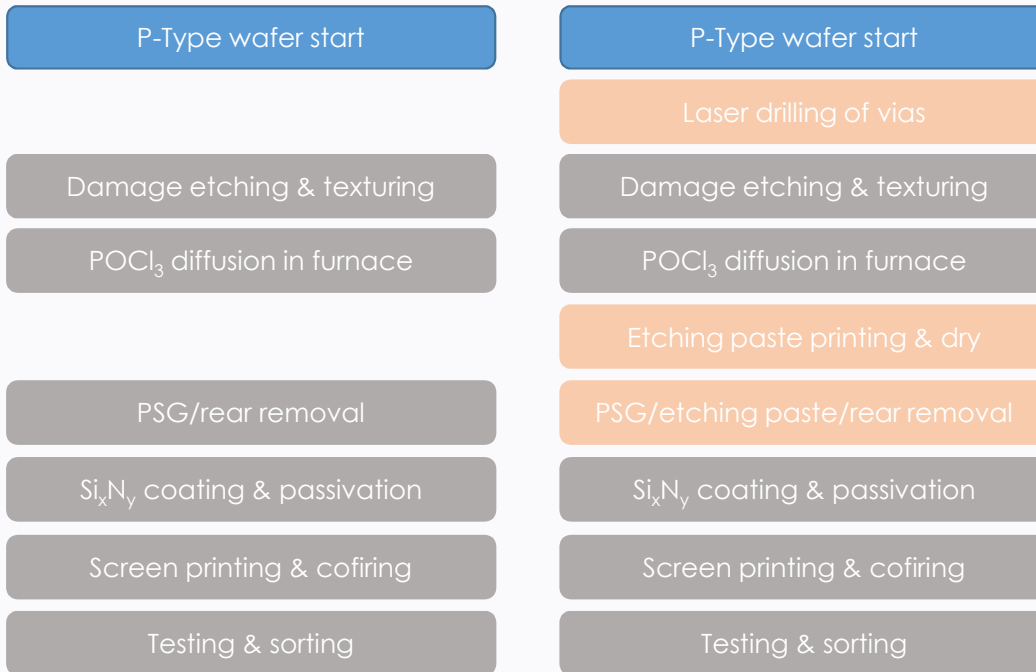
TC Condition:

85 °C ~ -40°C ~ 85°C @200hours



Metal Wrap Through Technology

Normal Screen Printing Process vs. MWT



After drilling holes

A big end up holes
Is better for paste's
filling, which is
necessary for hole
junction removal step
and contact printing
process

Metal Wrap Through Technology



“MWT + Nano-Tex” Technology

Strategic Partner : Sunport



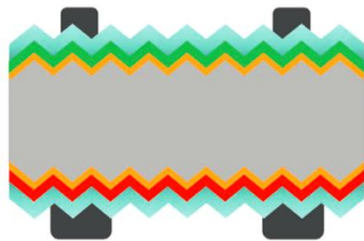
Module Capacity: 500 GW in Xuzhou City



HJT Technique & Performance

Advantages & Disadvantages between N type HJT & P type

Type	N Type HIT	P Type
Advantages	<ol style="list-style-type: none"> 1. No LID & No PID 2. Lower temperature coefficient 3. Bifacial structure 4. Higher conversion efficiency, easier over 22% 	<ol style="list-style-type: none"> 1. Mature process flow 2. More supplier for mass production 3. Lower cost
Disadvantages	<ol style="list-style-type: none"> 1. Higher process requirement 2. Small process windows 3. Cost more for tools and material 	<ol style="list-style-type: none"> 1. Some LID & PID issue 2. Hard to achieve efficiency over 22%



front grid
 front TCO
 i/p-a-Si:H "emitter"
 n-type wafer
 i/n-a-Si:H "BSF"
 rear TCO
 rear grid

Cell Type	P-Poly	P-Mono	N-HIT
Cell Efficiency	19%	21%	22%
Ideal module efficiency	17.22%	18.68%	19.57%
CTM loss	1-2%	3.5-4%	<2%
Real module efficiency	16.87%	17.94%	19.18%
LID	1%	2%	N
PID	Y	Y	N
Temperature coefficient (%/°C)	-0.45	-0.45	-0.27
PTC/STC	89.20%	89.00%	93.00%
Efficient module efficiency	14.60%	15.33%	17.83%

HJT Technique & Performance

● Wet Chemical Etching & Cleaning



● CVD Process for Junction



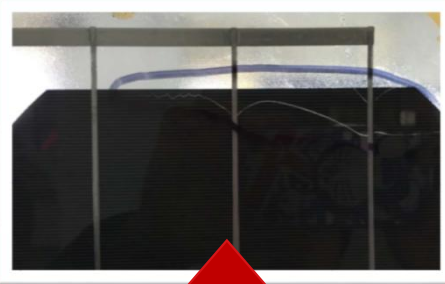
● Screen Printing for Metal Contact



● PVD Process for ITO



HJT Technique & Performance

Items	Progress	Result	Comment	Optimization Plan
CTM	Done	Average CTM 3.35% The range is 3.17%~3.74%	For mono P type production, CTM avg is 3.5%	1.Use high transparent glass 2.Optimize the soldering process 3.Refining the sorting BIN
LID	Done	30–35kWh be stable , 1.9% , range:1.2%~2.8%	Higher than P mono	1.Retest the sample 2. Change different simulator
Temperature Coefficient	Done	$\alpha=0.02\%$, $\beta=-0.28\%$ $\delta=-0.32\%$	Normal P type cell: $0.02\%/^{\circ}\text{C}$ 、 $-0.32\%/^{\circ}\text{C}$ 、 $-0.46\%/^{\circ}\text{C}$	 <p>Some crack happened near the beginning of solder strip</p>
Low Irradiation	Done	200W/m ² : ↓80.8%	P type average: ↓80.5%	
DH	Done	DH1000, ↓2.19%	IEC61215 & internal control rule: after DH2000, TC400, Power degradation < 5%, no appearance issue	
TC	Done	TC400, ↓3.54%		

HJT Technique & Performance

HJT bifacial power generating performance testing site



HJT Technique & Performance

HJT bifacial module power generation site experiment with different landform (one year data)

Landform	Power output kWh	kWh/W	Power output gain	Analysis	Future Plan
White backsheet	316.99	0.0545	1.15 (15%)	Result highly fit the reflection coefficient of the landform	White paint & white stone might be a cost effective solution for increasing the Rearside light absorbing
White paint	314.21	0.05375	1.13 (13%)		
White stone	309.19	0.0529	1.12 (12%)		
Water	297.26	0.0508	1.07 (7%)		
Cement (baseline)	276.24	0.0474	1.00		
Grass	267.54	0.0461	0.97		

HJT single side module vs. HJT bifacial

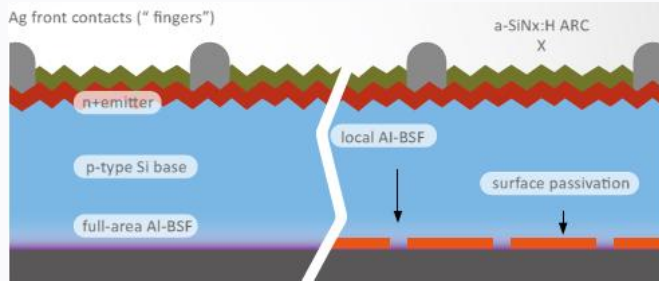
Module type	Power output kWh	kWh/W	Power output gain	Analysis	Future Plan
Single side	176.42	0.0304	1.038(3.8%)	Backsheet reflectance is considerable for single side HJT	Compare black and white backsheet
Bifacial	170.74	0.0293	1.00		

HJT single side module vs. Normal P type poly

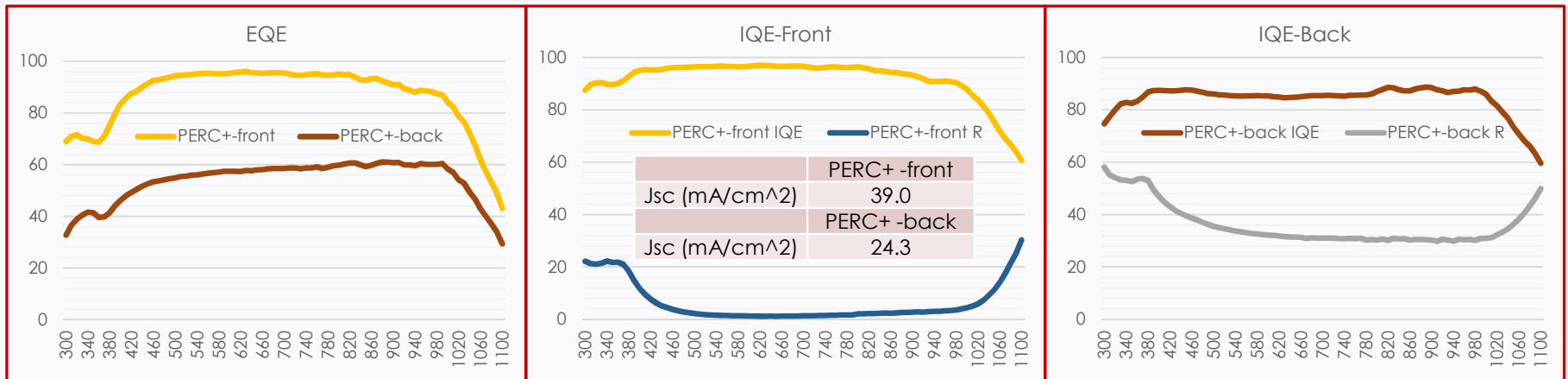
Module type	Power output kWh	kWh/W	Power output gain	Analysis*
HJT single side	176.42	0.0304	1.045(4.5%)	1、 gain from the backside (backsheet reflectance) 2、 lower temperature coefficient. (HIT-0.32%)(P type-0.46%)
Normal	155.03	0.0291	1.00	

PERC+ Research

PERC+ process and performance research

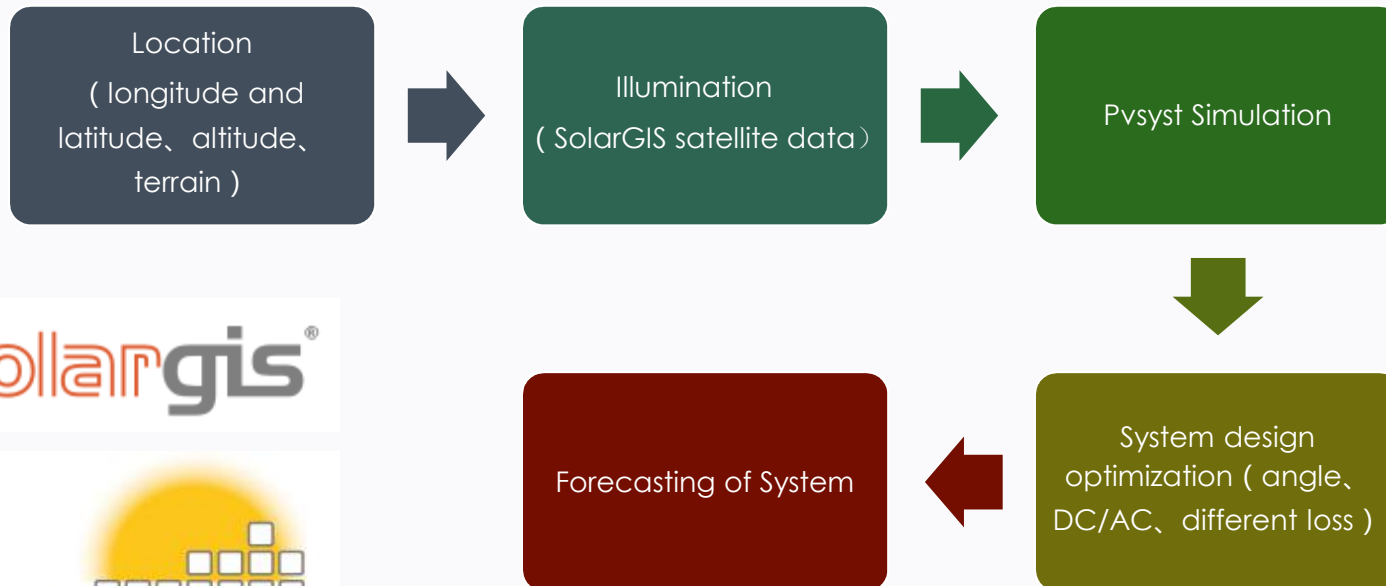


p-PERC	Contrast items	PERC+
Yes	Rear SixNy layer	No
Yes	Laser grooving	No
About 20nm (TMA consumption higher)	Al ₂ O ₃ (TMA consumption)	About 6nm (TMA consumption lower)
No	Bifacial cell	Yes (bifacial coefficient>75%)
20.5%	Conversion efficiency	20.3% (lab result)
Full print , high	Al paste consumption	Grid print ,low

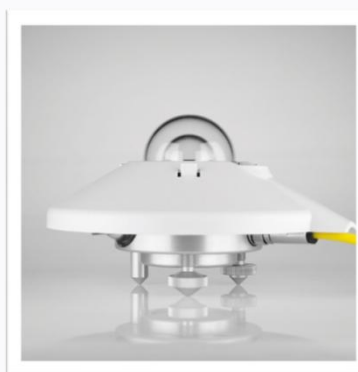
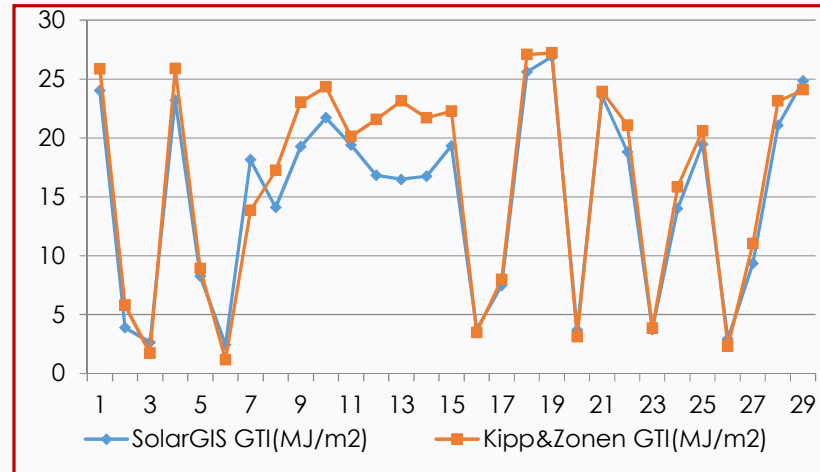


PV System Forecasting

SolarGIS Data + Pvsyst Simulation + Empirical Correction



PV System Forecasting



The Satellite Data is not very accuracy especially there is any microclimate change at the location.

So, we installed high accurate Solar radiation measurement tools to fix SolarGIS' data.

PART 3. PV Plant case

- Ground Mounted PV Plant
- Distributed Power Plant
- Others

Marketing Strategy

上屋顶



Distributed Systems on
Rooftops

下农田



Abandoned Ground-
Mounted (seashore, coal-
mining subsidence area)

达用户



Standalone System

Ground-Mounted PV Plant

Project Overview

Location: Dongtai, Jiangsu

Project Type: Ground-Mounted

System Size: 50 MW

Completion Date: December 2013

Construction Period: 14 months

Generating Capacity: 58,613 MWh/year

China largest tidal-flat PV power plant



Distributed Power Plant

Project Overview

Location: Hefei, Anhui

Project Type: Distributed Rooftop

System Size: 100 MW

Completion Date: May 2016

Construction Period: 24 months

Generating Capacity: 48,930 MWh/year

China largest Distributed PV power plant



Others



Xuyi, 9.8MW.
hilly area, sheep farming



Peixian, 15.8MW.
Coal mining subsidence area

Others

Germany



America



Australia



Japan



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